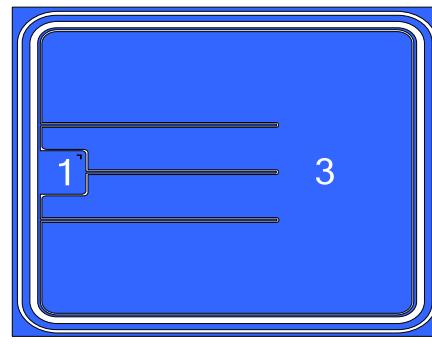


3VD499650YL HIGH VOLTAGE MOSFET CHIPS

DESCRIPTION

- 3VD499650YL is a High voltage N-Channel enhancement mode power MOS-FET chip fabricated in advanced silicon epitaxial planar technology;
- Advanced termination scheme to provide enhanced voltage-blocking capability;
- Avalanche Energy Specified;
- Source-to-Drain Diode Recovery Time Comparable to a Discrete Fast Recovery Diode;
- The chips may packaged in TO-220 type and the typical equivalent product is 12N65;
- The packaged product is widely used in AC-DC power suppliers, DC-DC converters and H-bridge PWM motor drivers;
- Die size: 5.66mm*4.4mm;
- Chip Thickness: $300\pm20\mu\text{m}$;
- Top metal: Al, Backside Metal: Ag.



1-Gate PAD 3-Source PAD

CHIP TOPOGRAPHY

ABSOLUTE MAXIMUM RATINGS ($T_{\text{amb}}=25^\circ\text{C}$)

Parameter	Symbol	Ratings	Unit
Drain-Source Voltage	V_{DS}	650	V
Gate-Source Voltage	V_{GS}	± 30	V
Drain Current	I_D	12	A
Power Dissipation (TO-220 Package)	P_D	180	W
Operation Junction Temperature	T_J	150	$^\circ\text{C}$
Storage Temperature	T_{stg}	-55~+150	$^\circ\text{C}$

ELECTRICAL CHARACTERISTICS ($T_{\text{amb}}=25^\circ\text{C}$)

Parameter	Symbol	Test conditions	Min.	Typ.	Max.	Unit
Drain -Source Breakdown Voltage	$BVDSS$	$V_{GS}=0\text{V}$, $I_D=250\mu\text{A}$	650	-	-	V
Gate Threshold Voltage	V_{TH}	$V_{GS}=V_{DS}$, $I_D=250\mu\text{A}$	2.0	-	4.0	V
Drain-Source Leakage Current	$Idss$	$V_{DS}=650\text{V}$, $V_{GS}=0\text{V}$	-	-	1.0	μA
Static Drain- Source On State Resistance	$R_{DS(on)}$	$V_{GS}=10\text{V}$, $I_D=6.0\text{A}$	-	-	0.8	Ω
Gate-Source Leakage Current	$IGSS$	$V_{GS}=\pm 30\text{V}$, $V_{DS}=0\text{V}$	-	-	± 100	nA
Source-Drain Diode Forward on Voltage	$VFSD$	$I_S=12\text{A}$, $V_{GS}=0\text{V}$	-	-	1.4	V